

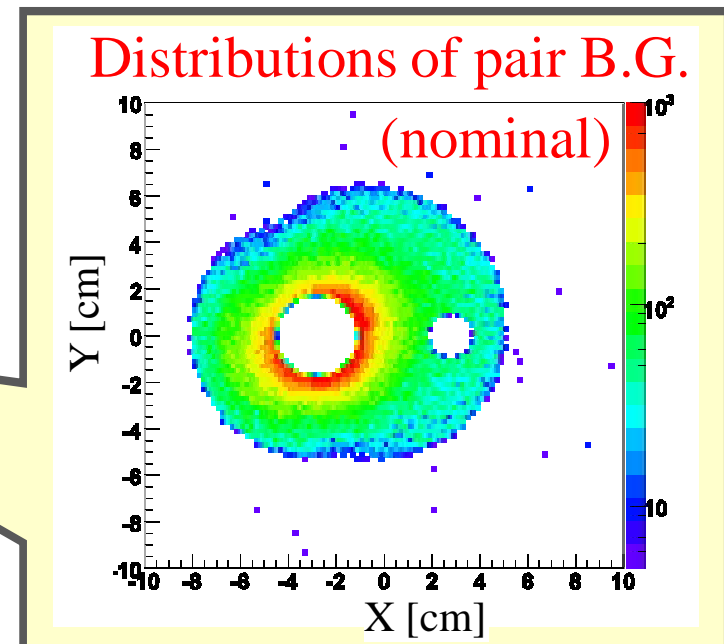
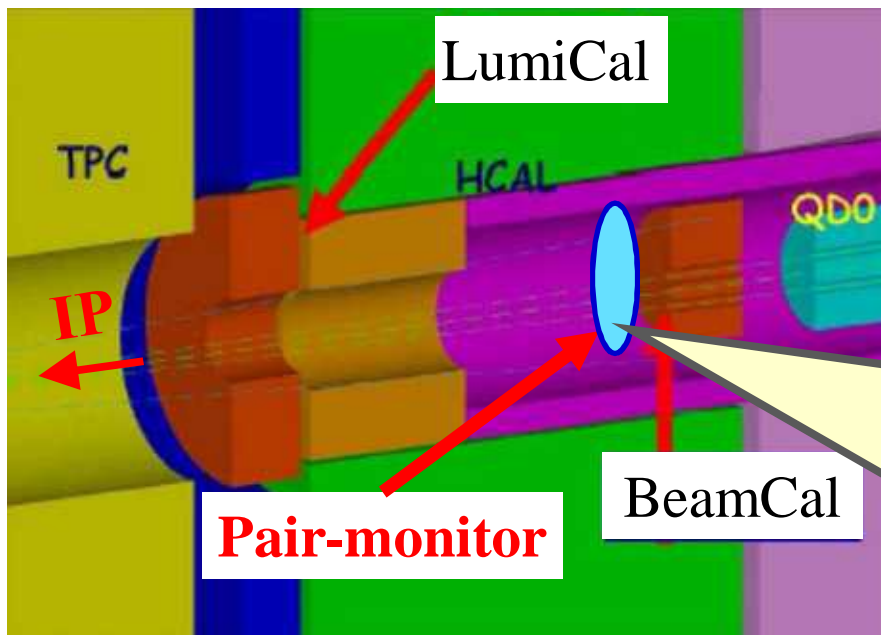
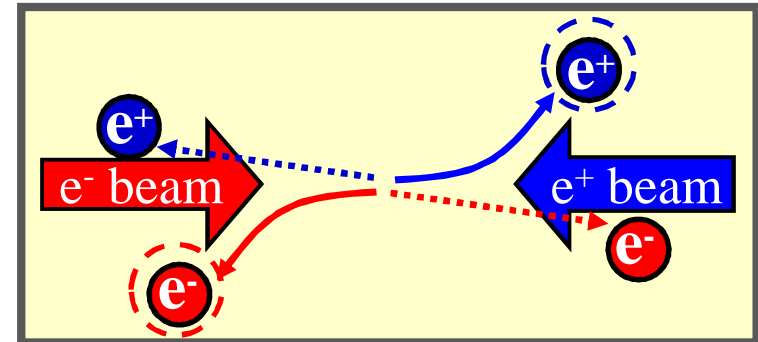
*The development of the readout ASIC
for the pair-monitor with SOI technology
~irradiation test~*

Yutaro Sato
Tohoku Univ.
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- ◆ Introduction
 - Pair-monitor
 - SOI technology
- ◆ Prototype ASIC
 - Design
 - Irradiation test

Pair-monitor is a silicon pixel detector to measure the beam profile at IP.

- The distribution of the pair B.G. is used.
 - The same charges with respect to the oncoming beam are scattered with large angle.
 - The scattered particles have information on beam shape.
- The location will be in front of the BeamCal.



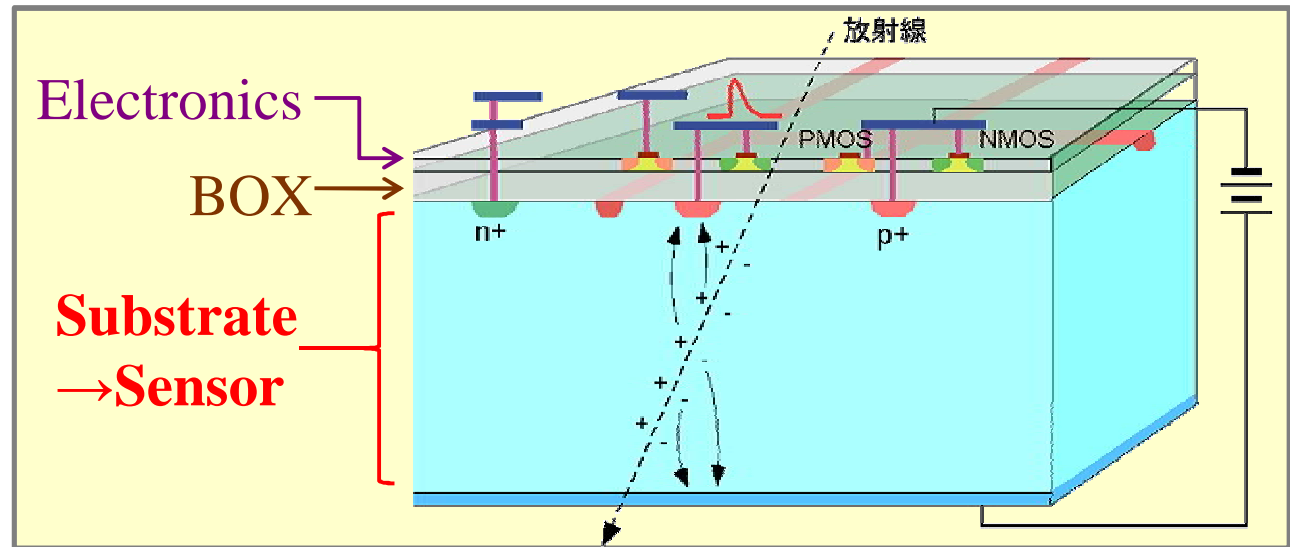
Development of Pair-monitor with SOI technology²

The pair-monitor is developed using the SOI technology.

SOI (Silicon On Insulator) pixel detector

- SOI pixel group at KEK is currently developing.
- The sensor and electronics are integrated in the SOI substrate.

- **Monolithic device**
- High speed
- Low power
- Thin device
- Low material

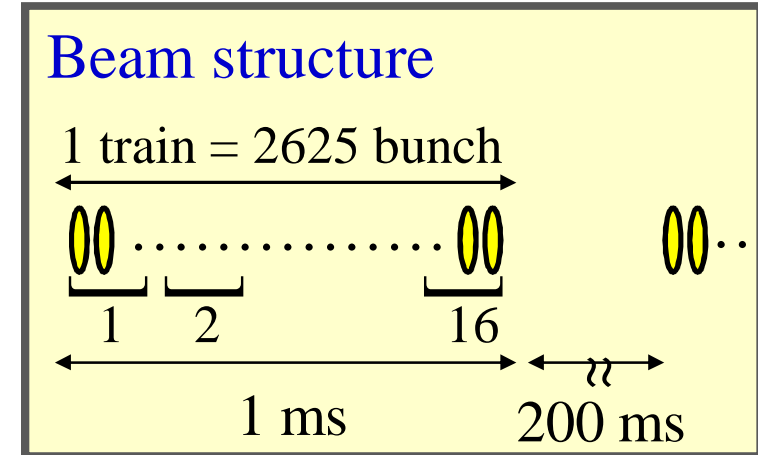


➔ The prototype ASIC for the pair-monitor was fabricated via the MPW Run organized by the SOI pixel group.

- This prototype is not monolithic (Substrate is not a sensor).

Required performance

1. Time resolution : **< 260 nsec**
(less than bunch space)
2. Noise level : **< 1000 e**
(typical signal level : 15,000 e)
3. Radiation tolerance : **> a few Mrad/year**
4. **Time-dependent** measurement
 - Measure the pixel hit count in 16 time slice per train,
and hit counts are read out during the inter-train gap of 200 ms.

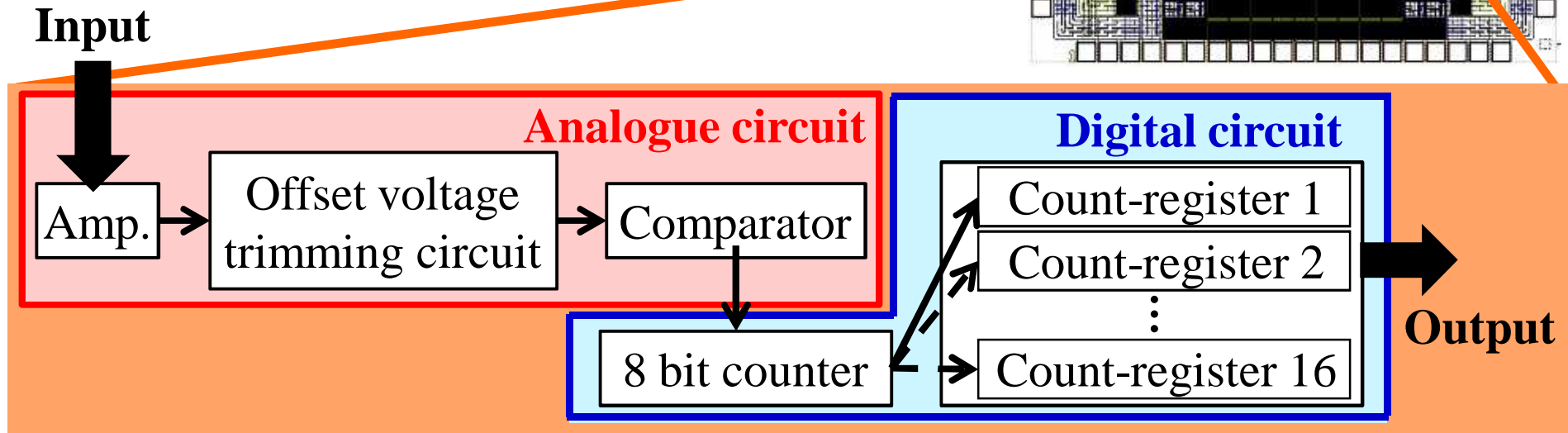
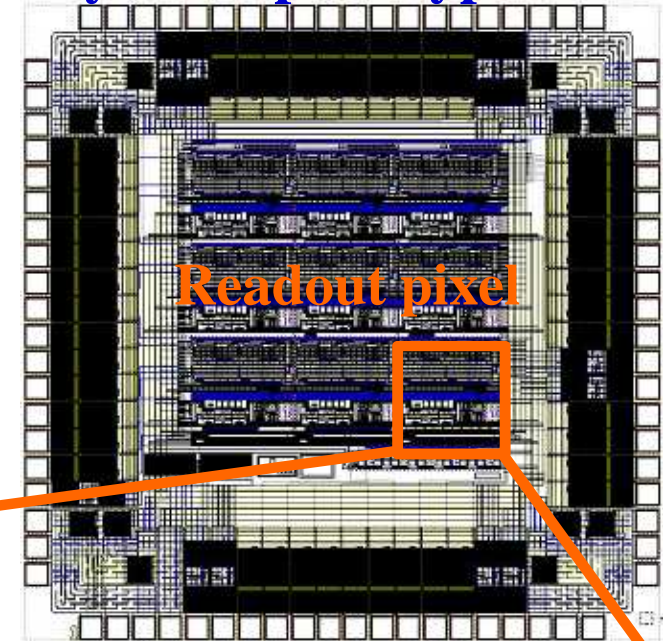


→ The prototype readout ASIC was designed to satisfy these requirements.

Prototype readout ASIC

- Process : FD-SOI CMOS 0.20 μm
- Chip size : 2.5 x 2.5 mm^2
- # of pixels : 9 (3x3)
- Pixel size : 390 x 350 μm^2
- Each cell has different detector capacitance.

Layout of prototype ASIC



Irradiation test

Irradiation test was performed to test the radiation tolerance and observe the radiation effect.

- X-ray generator : Rigaku FR-D
 - Target : Cu (~ 8 keV)
- Doses : up to 2 Mrad
 - #photons was evaluated
by the pin-diode.
 - All the photons are assumed to be absorbed within an attenuation length ($\lambda \sim 66 \mu\text{m}$).
 - Silicon density : $d = 2.33 \text{ g/cm}^3$



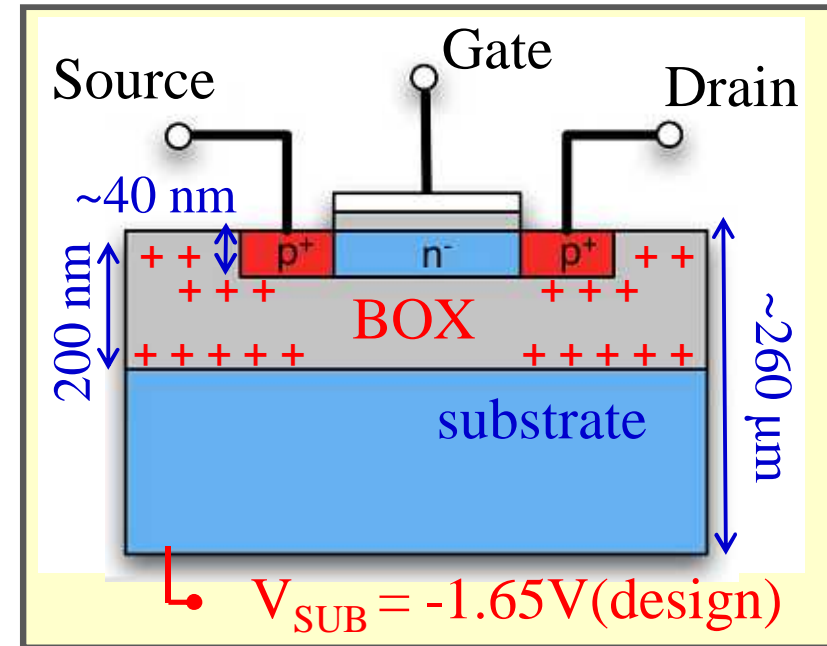
There are two types of radiation effect.

Single event effect (SEE)

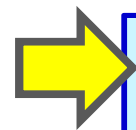
- Caused by single energetic particle.
- SOI device is known as rad-hard for SEE.

Total dose effect (TDE)

- Caused by charge trapped in the oxide layer.



→ Oxide trapped charge could be compensated by the substrate voltage.



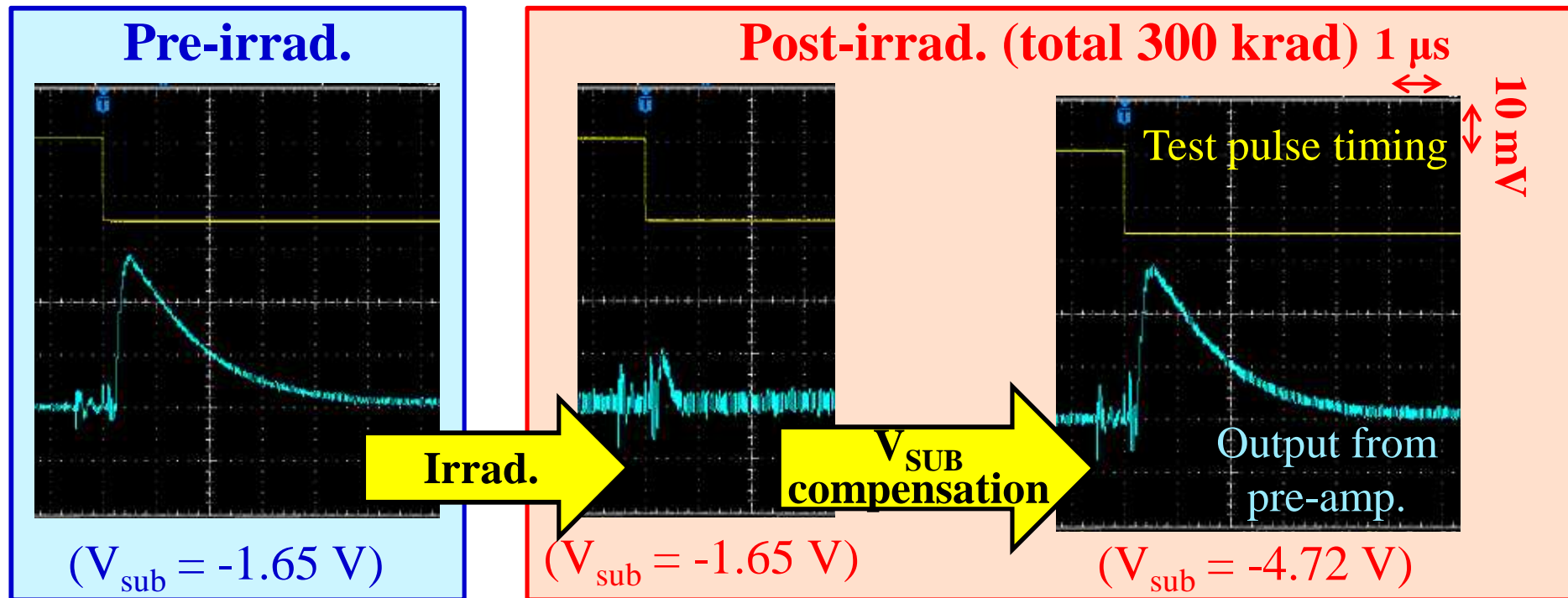
Performed measurements

Signal shape at pre-amp.
Gain
Linearity
Noise level

Signal shape

The signal shape at the pre-amp. was compared.

- By irradiation, the signal shape becomes smaller.



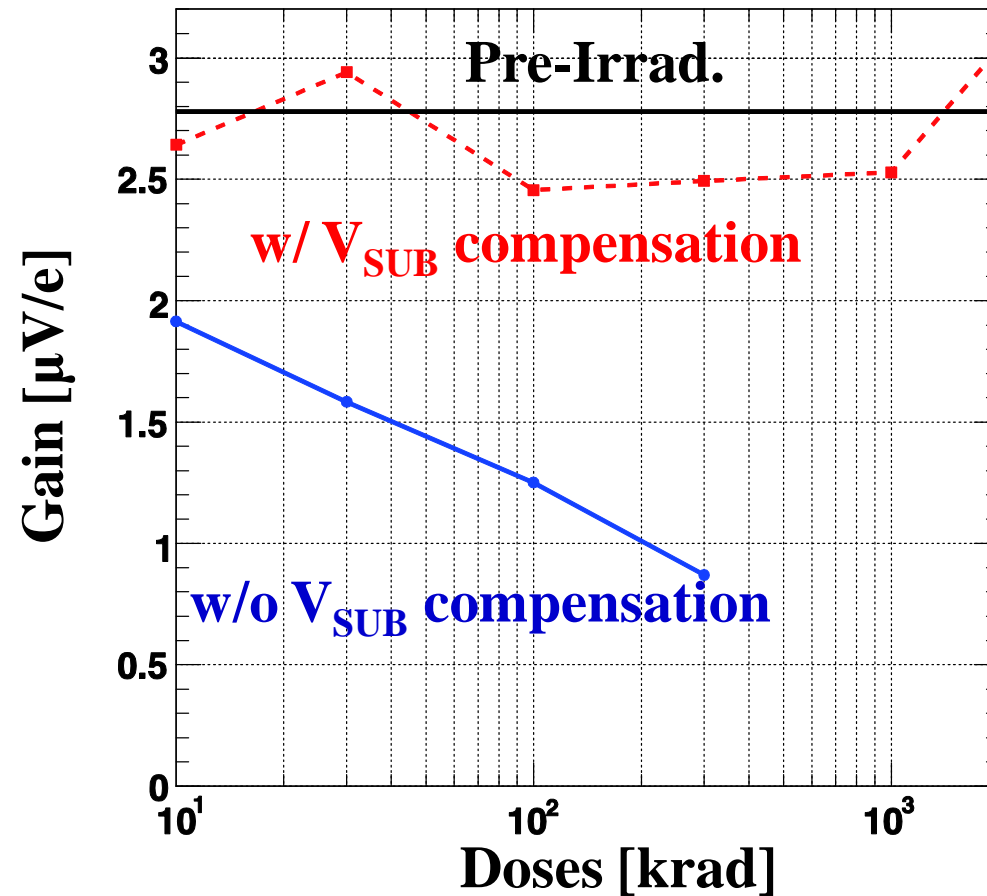
➔ The signal shape of post-irradiation can be returned to that of pre-irradiation by V_{SUB} compensation.

- The transistor was shorted due to large 1 Mrad irradiation, however similarly the signal shape can be returned by V_{SUB} .

Gain

The threshold scan was performed and the gain was compared.

- By the irradiation, the gain becomes smaller.

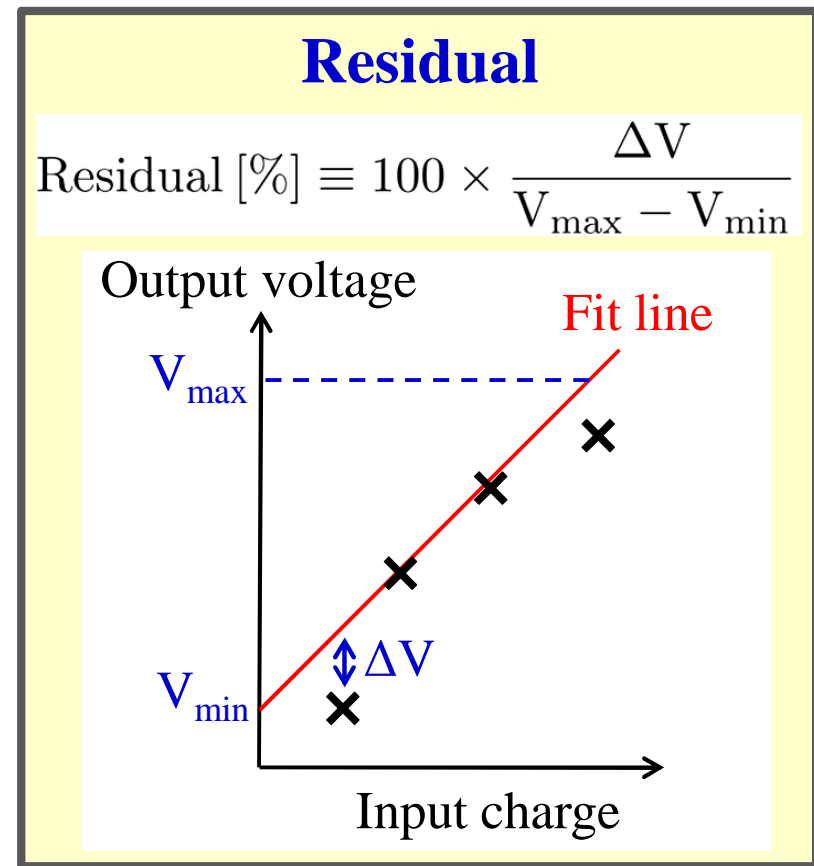
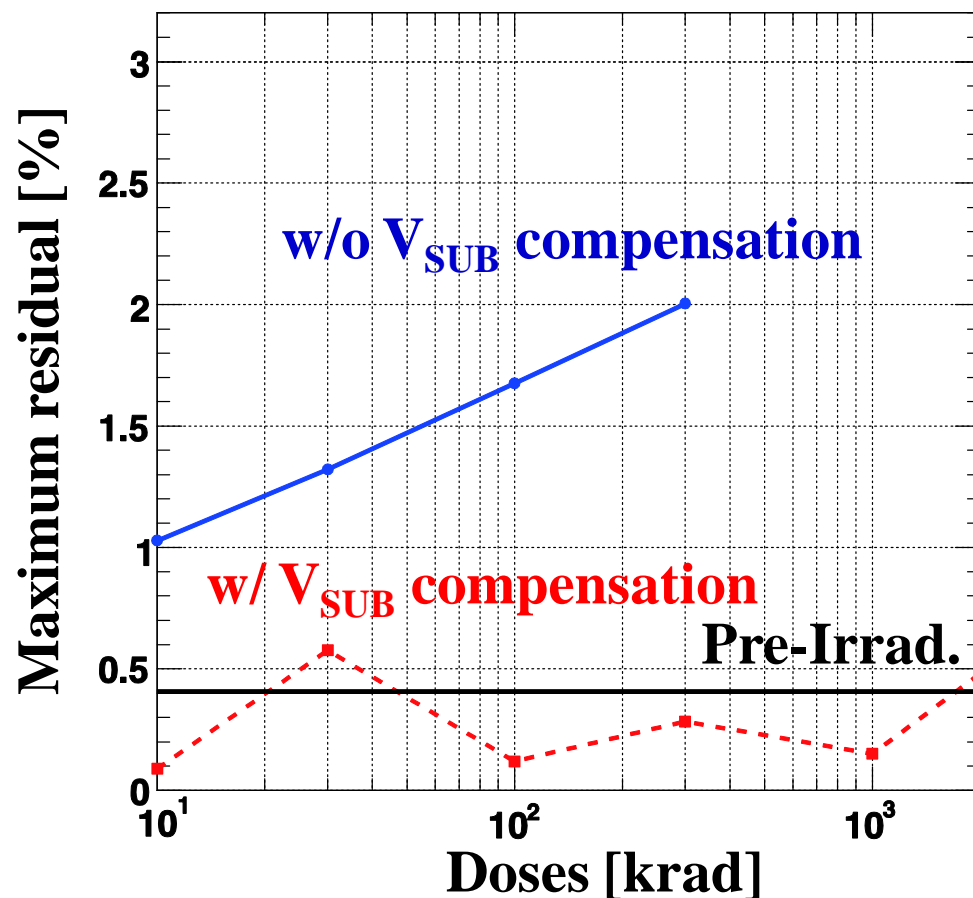


➔ The gain can be restored by V_{SUB} compensation.

The threshold scan was performed and the linearity was compared.

(fitting region : 7,000 ~ 45,000 e)

- By the irradiation, the linearity becomes worse.

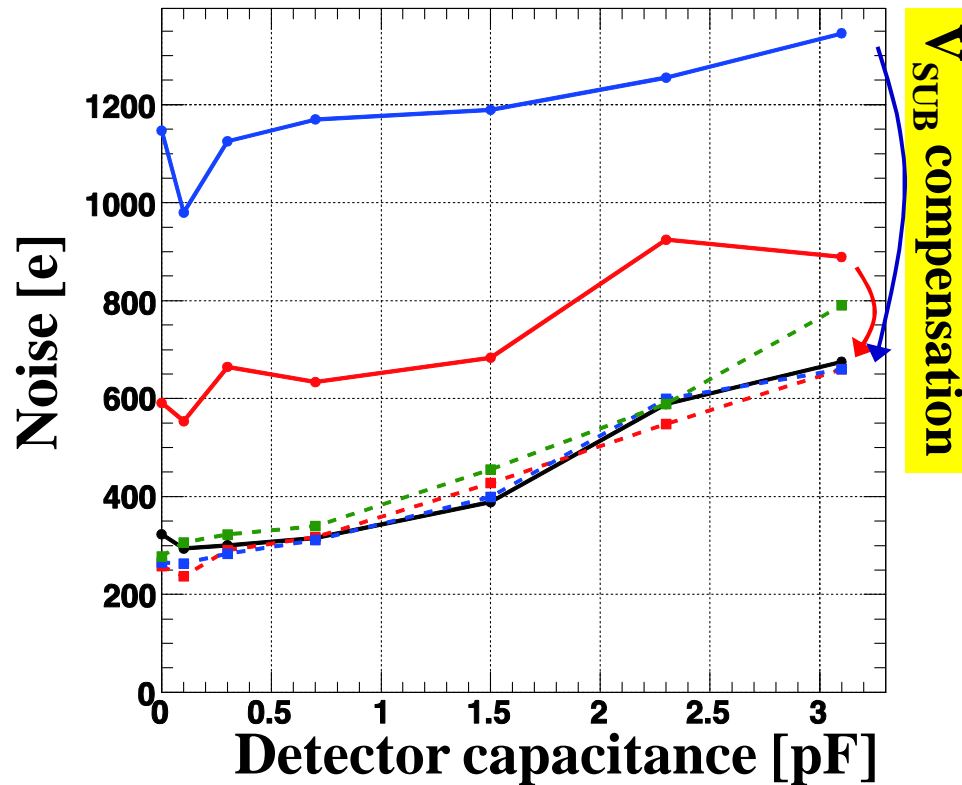


➔ The linearity can be restored by V_{SUB} compensation.

Noise level

The noise level was compared.

- By irradiation, the noise level becomes bigger.



Pre-Irrad.
Post-Irrad. (100krad)
Post-Irrad. (300krad)
Post-Irrad. (2Mrad)

Dashed line means
w/ V_{SUB} compensation.

→ The noise level returns to that at pre-irrad. by the V_{SUB} compensation.

→ The radiation tolerance up to 2 Mrad was confirmed and oxide trapped charge was compensated by V_{SUB} .

Summary

The development of the pair-monitor with SOI technology was started.

- The first prototype which is only readout ASIC was produced and **the irradiation test** were performed successfully.
 - The radiation tolerance up to 2 Mrad was confirmed.
 - The oxide trapped charge was compensated by the substrate voltage.

Plan

- Irradiation test (γ -ray or electron beam)
- Production of the monolithic prototype

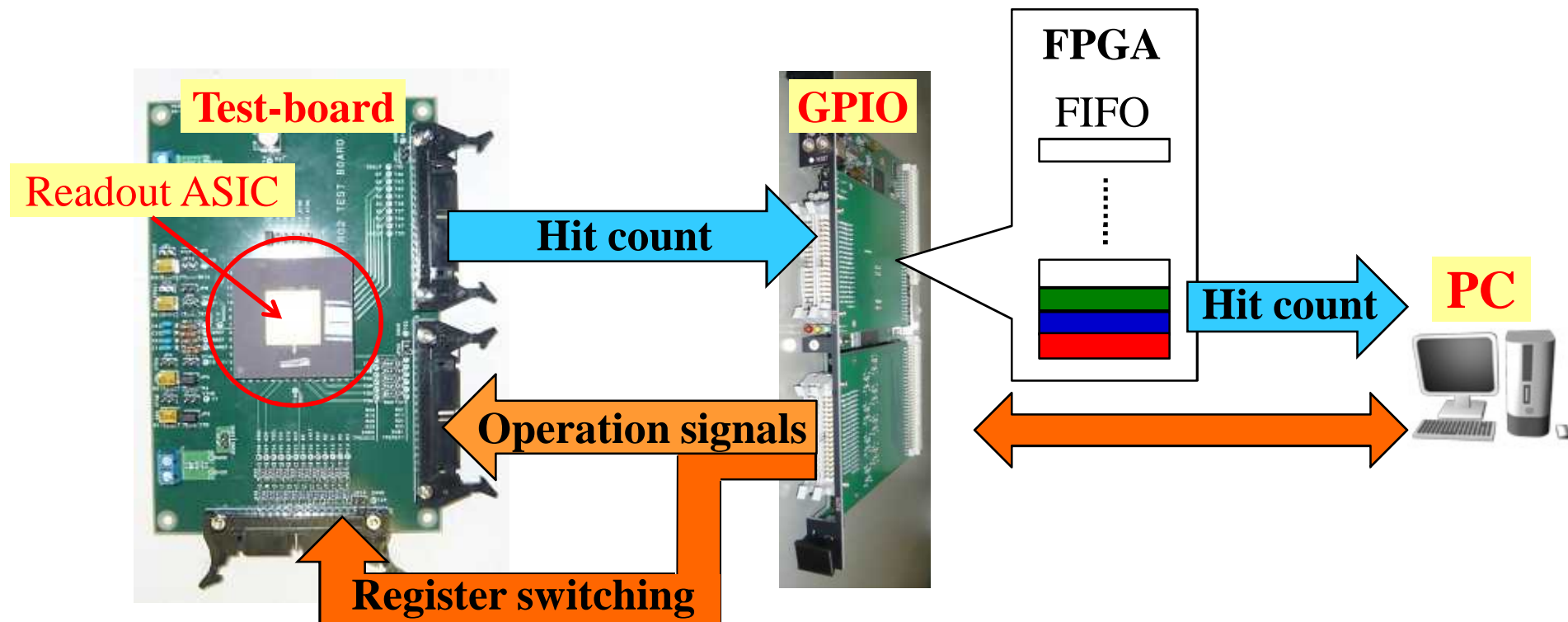
Backup

Test system

The operation test was performed.

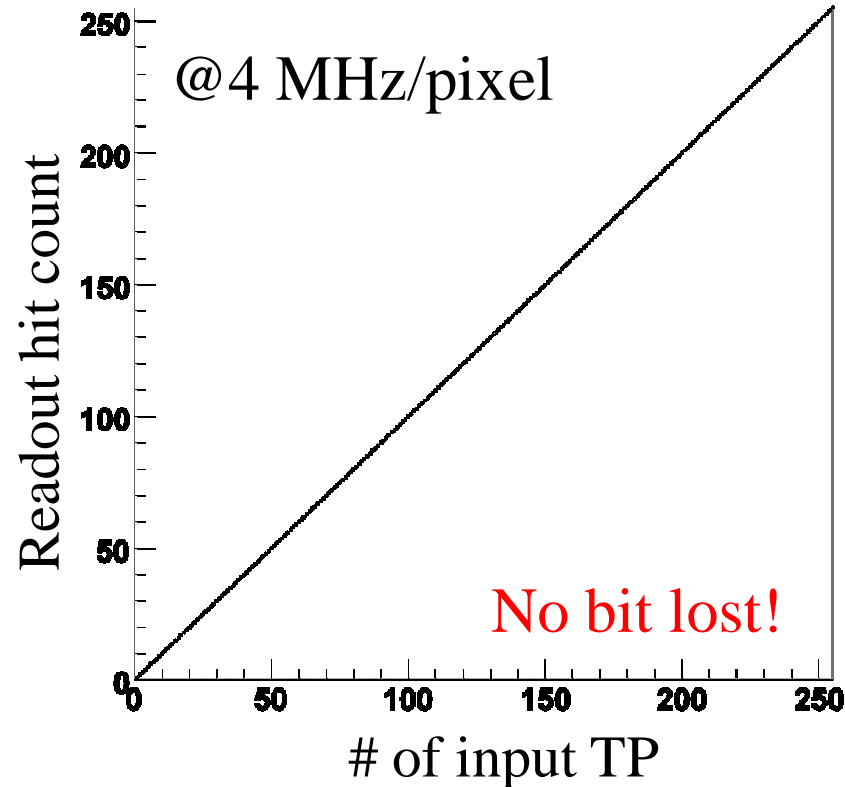
Test system

- GNV-250 module was used for the operation and readout .
 - KEK-VME 6U module
- The test-sequence by GPIO is controlled by a PC.

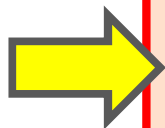
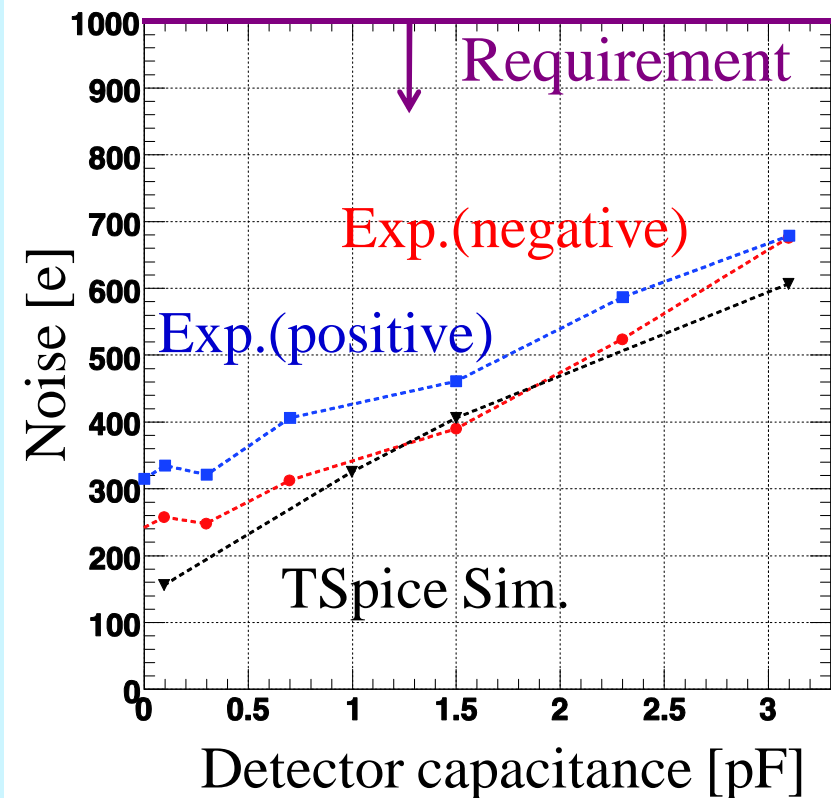


Operation test was performed successfully.

Time resolution & Time-dep. measurement



Noise level

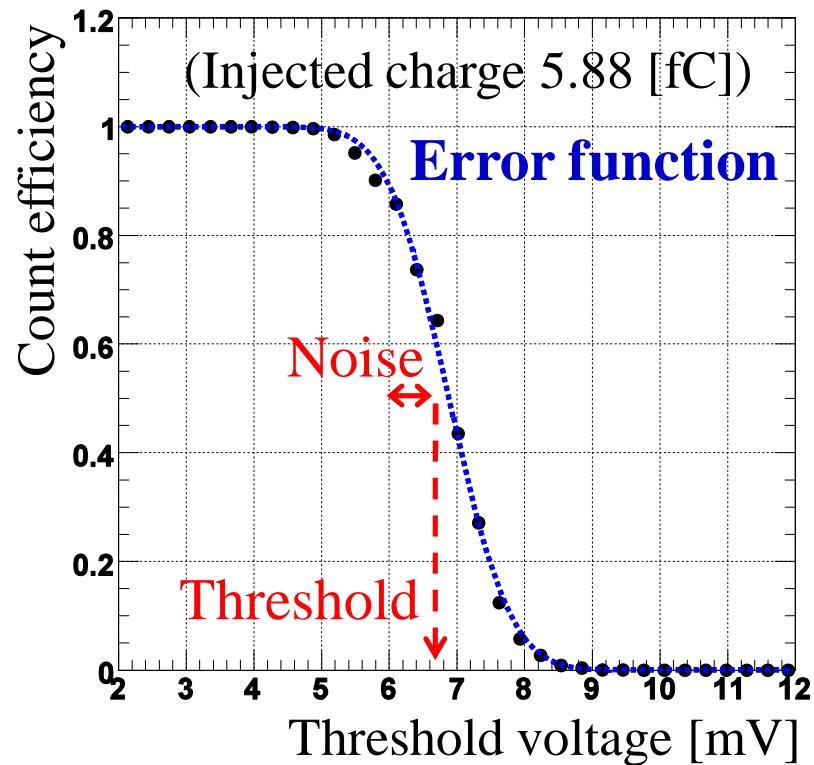


Prototype meets the requirement of time resolution, time-dependent measurement and noise level.

Threshold scan

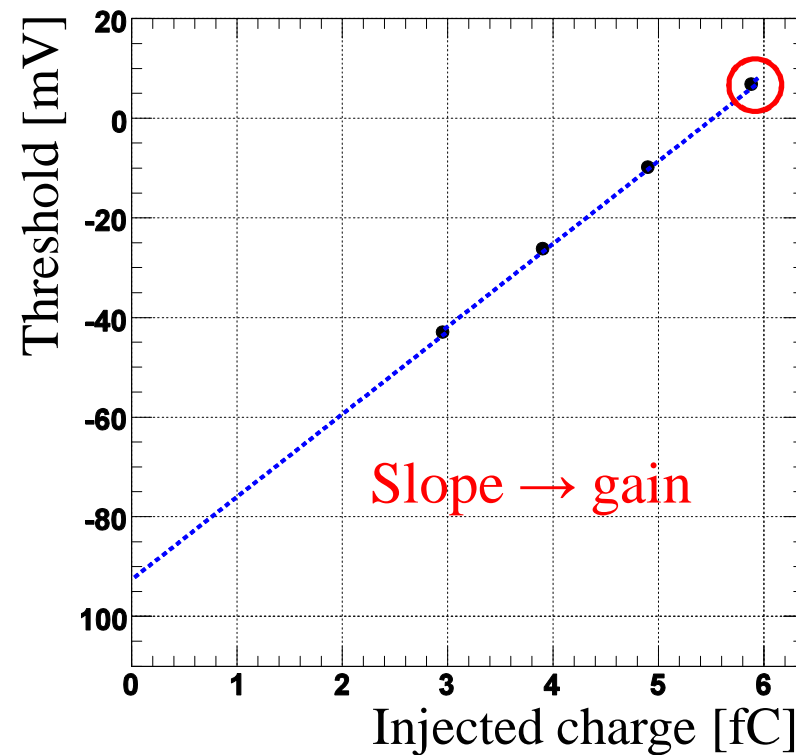
Threshold scan was performed.

- Fit to error function (S-curve)



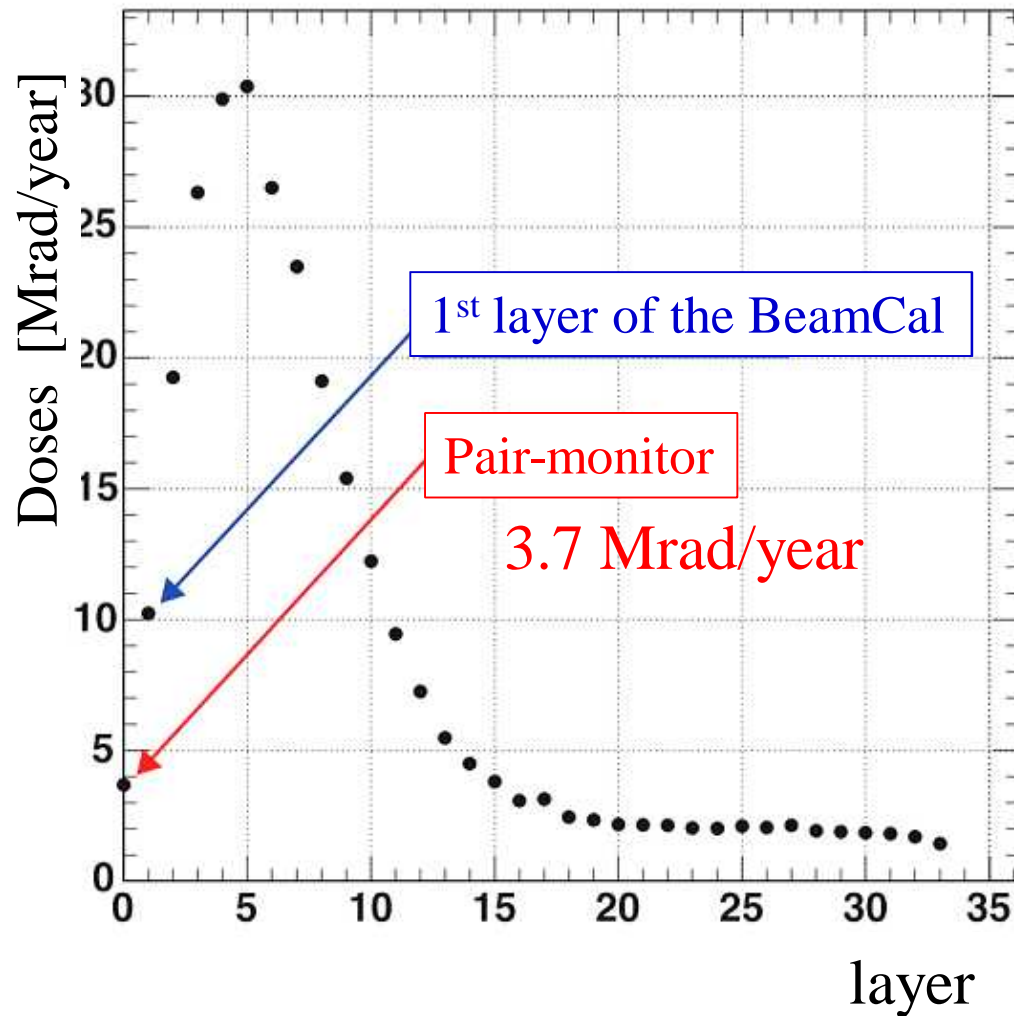
- Threshold : 6.886 ± 0.009 [mV]
- Noise : 0.7152 ± 0.0128 [mV]

The gain was estimated to convert the noise into equivalent noise electrons.



- Gain : 16.94 [mV/fC]

Noise : ~260 electrons



Radiation doses

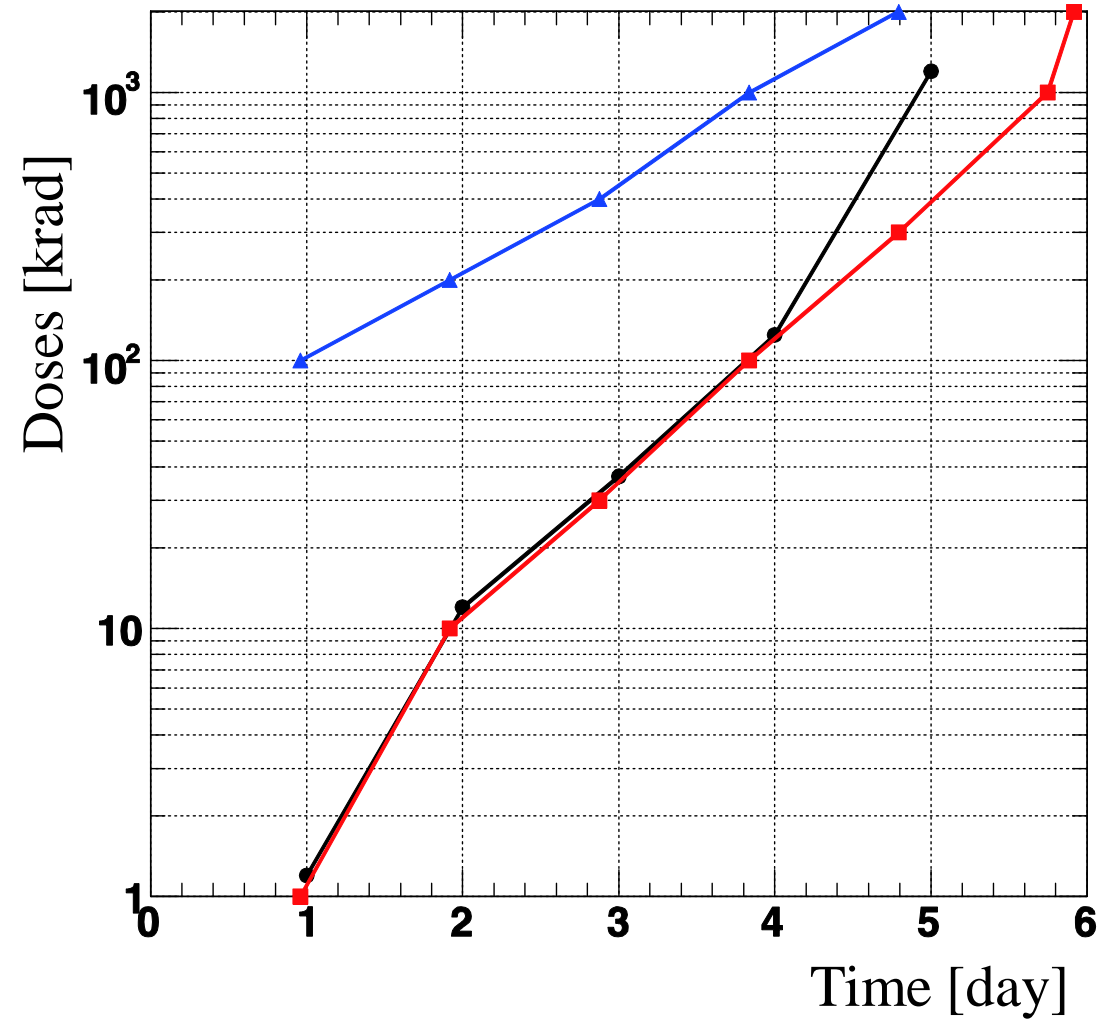
Total Doses = (#photon) × (Doses per a photon)

The number of photons

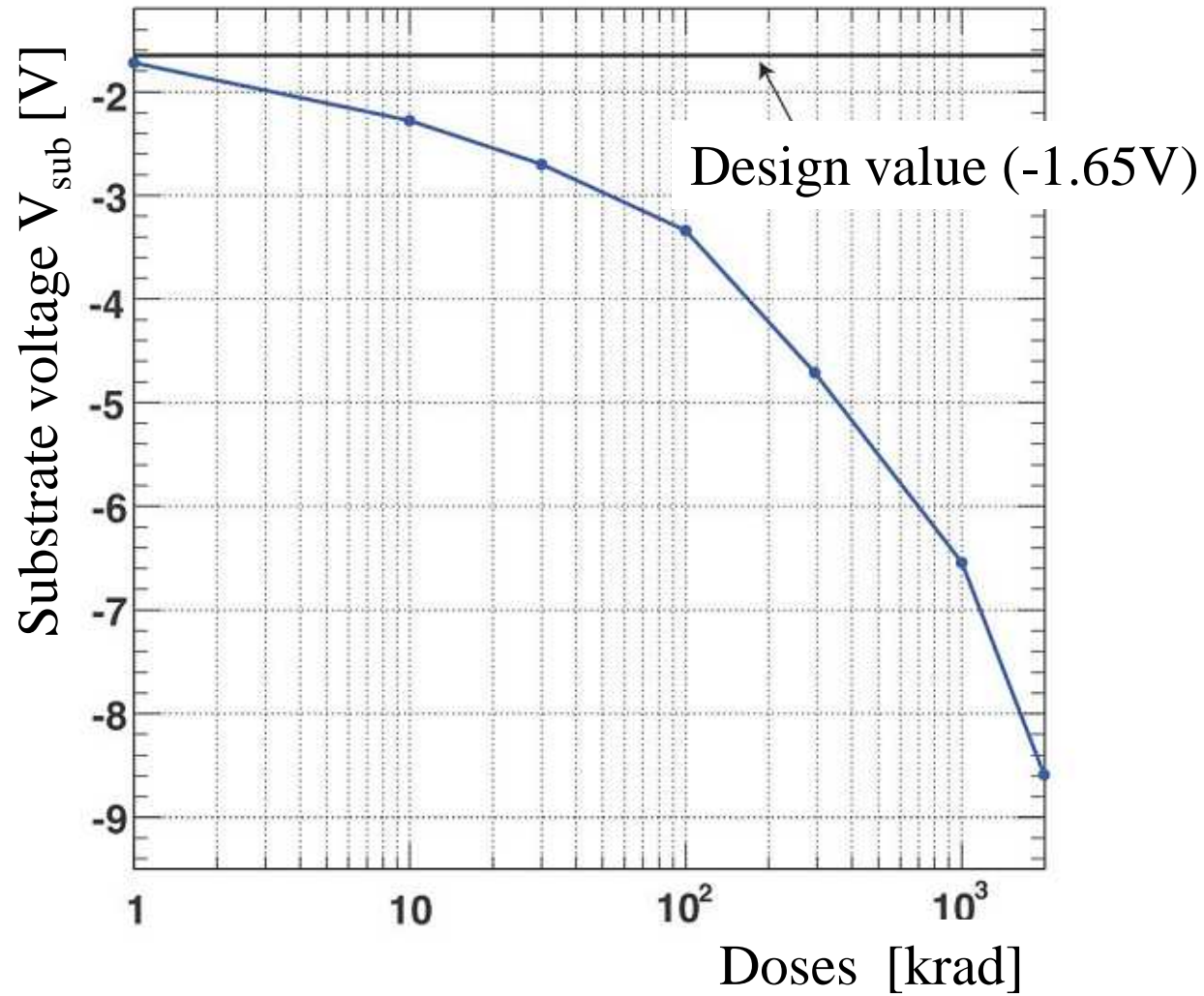
- Evaluated by the photoelectron of diode.
 - $k = 2.5 \times 10^9$ [photon/ μA]

Doses per a photon

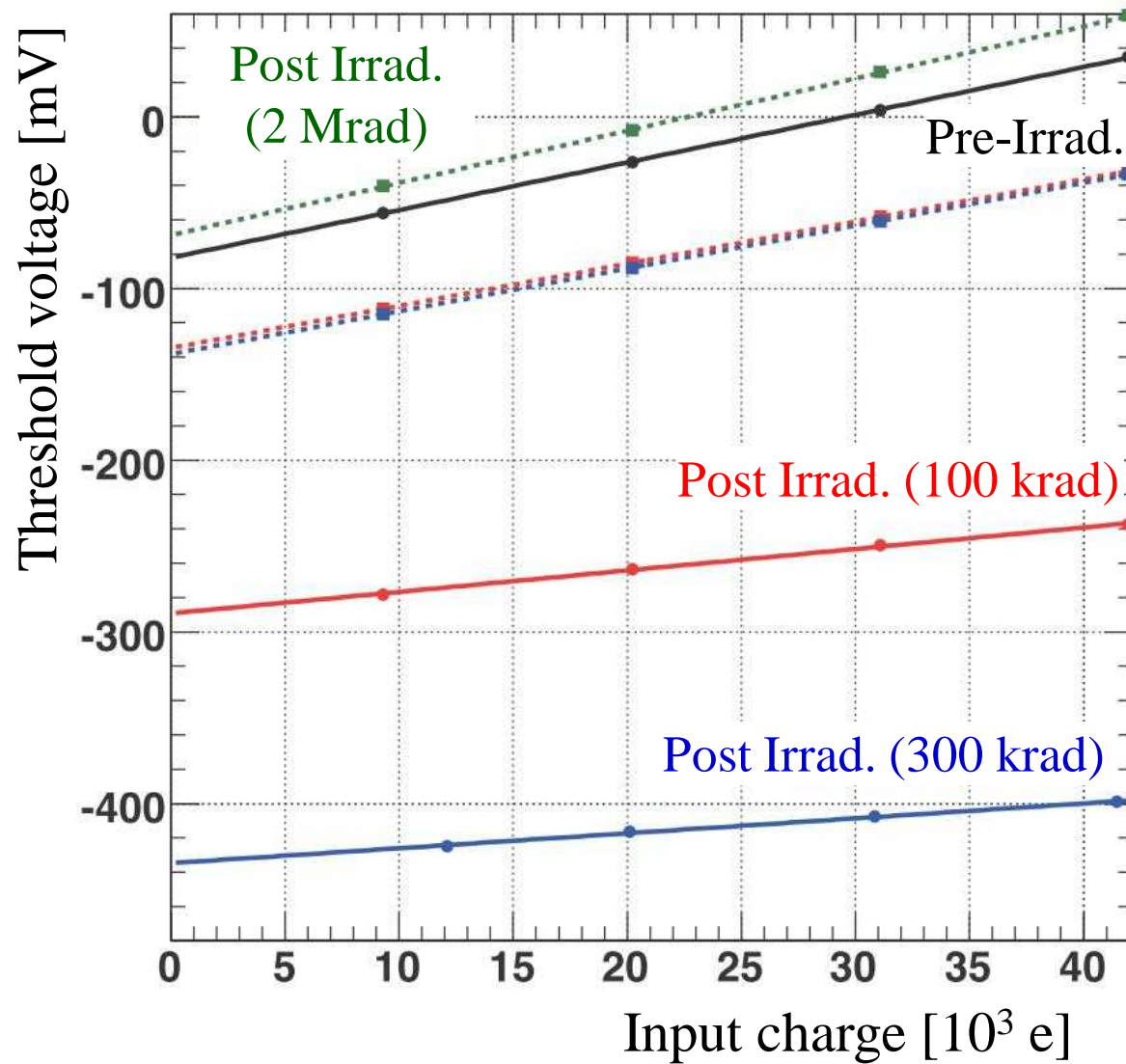
- Energy of photon : 8.19 keV
 - Weighted average of $K\alpha$ (8.04 keV) and $K\beta$ (8.91 keV)
 - All the photons are assumed to be absorbed within an attenuation length ($\lambda \sim 66 \mu\text{m}$)
- Silicon density $d = 2.33 \text{ g/cm}^3$



Substrate voltage (V_{sub})



Threshold scan



Residual

